

Joseph P, Klesko

List of Publications by Year in Descending Order

Source: <https://exaly.com/author-pdf/9091247/joseph-p-klesko-publications-by-year.pdf>

Version: 2024-04-04

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.

The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

12

papers

193

citations

8

h-index

12

g-index

12

ext. papers

223

ext. citations

7.7

avg, IF

3.2

L-index

#	Paper	IF	Citations
12	Reactivity of Atomic Layer Deposition Precursors with OH/H ₂ O-Containing Metal Organic Framework Materials. <i>Chemistry of Materials</i> , 2019 , 31, 2286-2295	9.6	11
11	Mechanistic study of the atomic layer deposition of scandium oxide films using Sc(MeCp) ₂ (Me ₂ pz) and ozone. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 011504	2.9	2
10	Low Temperature, Selective Atomic Layer Deposition of Nickel Metal Thin Films. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 14200-14208	9.5	21
9	Selective Atomic Layer Deposition Mechanism for Titanium Dioxide Films with (EtCp)Ti(NMe ₂) ₃ : Ozone versus Water. <i>Chemistry of Materials</i> , 2018 , 30, 970-981	9.6	14
8	Selective Growth of Interface Layers from Reactions of Sc(MeCp)(Mepz) with Oxide Substrates. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 32818-32827	9.5	2
7	Thermal Atomic Layer Etching of Silica and Alumina Thin Films Using Trimethylaluminum with Hydrogen Fluoride or Fluoroform. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 31784-31794	9.5	9
6	Substrate selectivity in the low temperature atomic layer deposition of cobalt metal films from bis(1,4-di-tert-butyl-1,3-diazadienyl)cobalt and formic acid. <i>Journal of Chemical Physics</i> , 2017 , 146, 052813 ³⁹	9.5	29
5	Low Temperature, Selective Atomic Layer Deposition of Cobalt Metal Films Using Bis(1,4-di-tert-butyl-1,3-diazadienyl)cobalt and Alkylamine Precursors. <i>Chemistry of Materials</i> , 2017 , 29, 7458-7466	9.6	34
4	Low Temperature Thermal Atomic Layer Deposition of Cobalt Metal Films. <i>Chemistry of Materials</i> , 2016 , 28, 700-703	9.6	48
3	Unusual stoichiometry control in the atomic layer deposition of manganese borate films from manganese bis(tris(pyrazolyl)borate) and ozone. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 051515	2.9	2
2	Thermal Atomic Layer Deposition of Titanium Films Using Titanium Tetrachloride and 2-Methyl-1,4-bis(trimethylsilyl)-2,5-cyclohexadiene or 1,4-Bis(trimethylsilyl)-1,4-dihydropyrazine. <i>Chemistry of Materials</i> , 2015 , 27, 4918-4921	9.6	20
1	Metallic Materials Deposition: Metal-Organic Precursors Update based on the original article by Charles H. Winter, Wenjun Zheng and Hani M. El-Kaderi, Encyclopedia of Inorganic Chemistry Second Edition, © 2005, John Wiley & Sons, Ltd. 2012 ,		1